



# Modulation of electron transport in single layer transition-metal dichalcogenides

Mahdi Ghorbani-Asl<sup>1</sup>, P. Miró<sup>1</sup>, Andrey M. Enyashin<sup>2,3</sup>, Tommy Lorenz<sup>2</sup>, Agnieszka Kuc<sup>1</sup>, Thomas Heine<sup>1</sup>

<sup>1</sup>School of Engineering and Science, Jacobs University Bremen, Germany

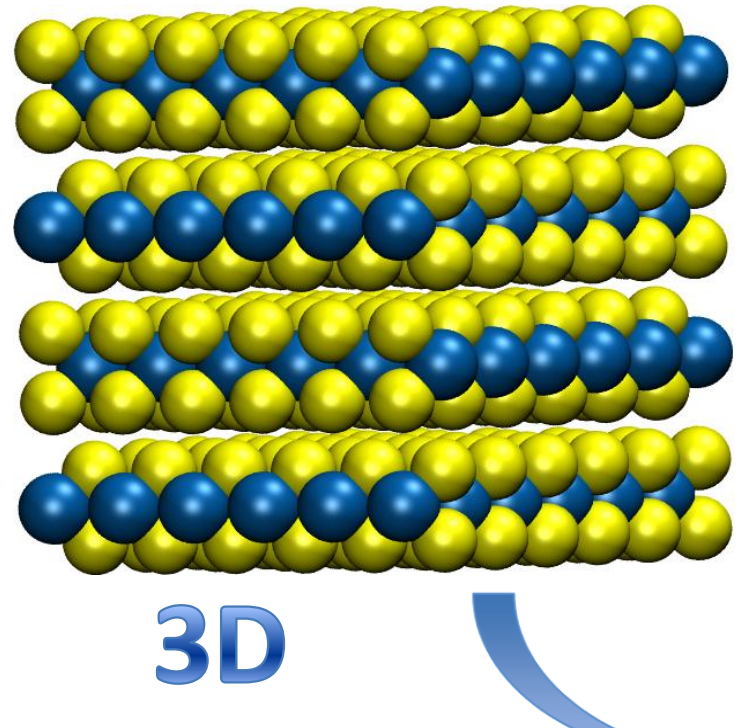
<sup>2</sup>Theoretische Chemie, Technische Universität Dresden, Dresden, Germany

<sup>3</sup>Institute of Solid State Chemistry UB RAS, Ekaterinburg, Russia

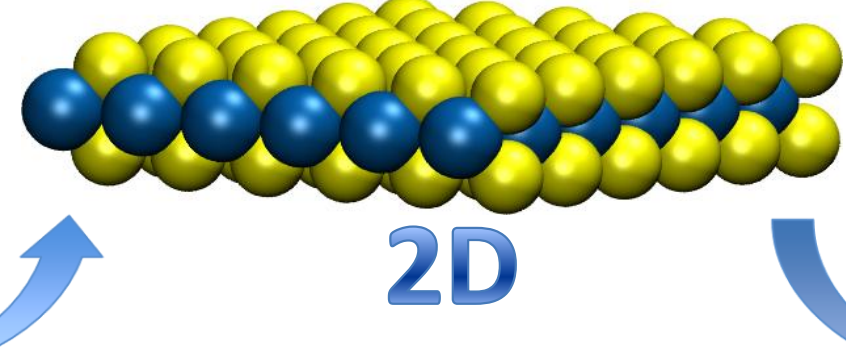
## Abstract

Transition-metal dichalcogenides  $\text{TX}_2$  (T=Mo, Nb, Ta, Re, Hf, W and X=Se, S, Te) may become alternatives to carbon based materials in nano-electronics. Recently, a series of electronic devices have been fabricated using a single layer of  $\text{MoS}_2$ , presenting promising potential for the next generation electronics. Using density functional based tight-binding (DFTB) method combined with the non-equilibrium Green's function formalism, we have studied electron transport in low-dimensional structures of transition-metal dichalcogenides.

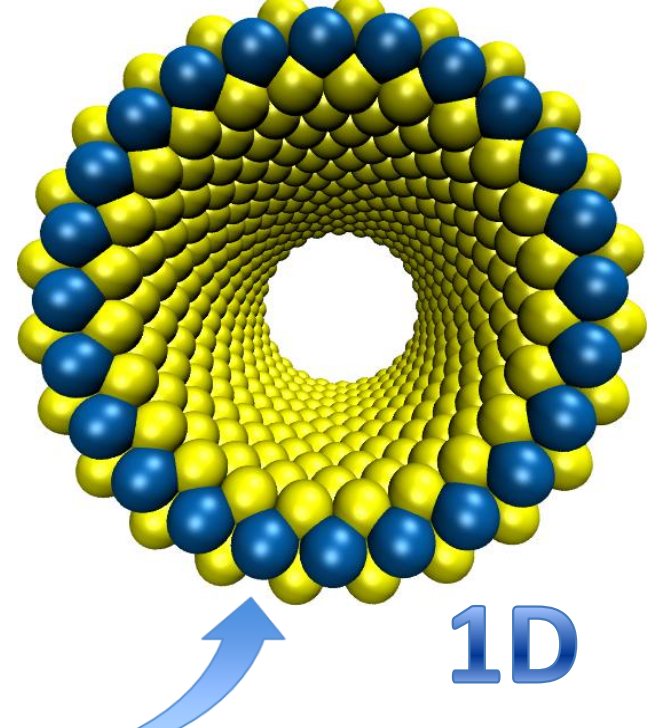
Exp. literature well-known for last 40 years



Recent exp. by:  
Kis and co-workers (*Nat. Nanotechnol.* 6, 147 (2012))  
Nicolosi and co-workers (*Science* 311, 568 (2011))



Exp. known since 1992:  
Tenne and co-workers (*Nature* 360, 444 (1992))



## Formalism

Green's function of an extended system

$$\tilde{G}_C(E) = [ES_C - \underbrace{H_C}_{\text{DFTB}} - \tilde{S}_L(E) - \tilde{S}_R(E)]^{-1} \quad \tilde{G}_{L(R)} = i[\tilde{S}_{L(R)} - \tilde{S}_{L(R)}^+]$$

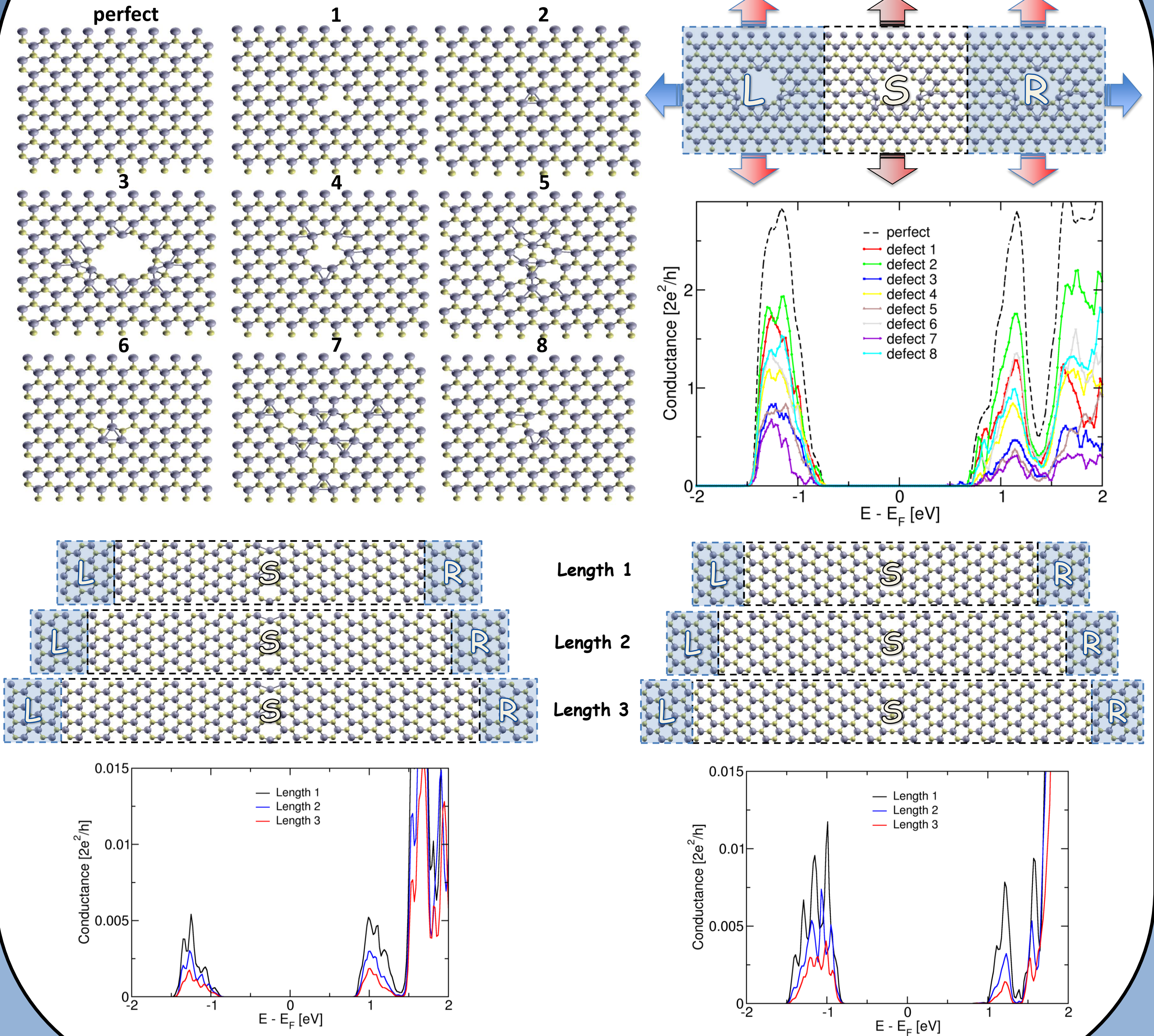
Transmission

$$T(E) = \sum_n T_n(E) = \text{Tr}[\tilde{G}_C^+(E)\tilde{G}_R(E)\tilde{G}_C(E)\tilde{G}_L(E)]$$

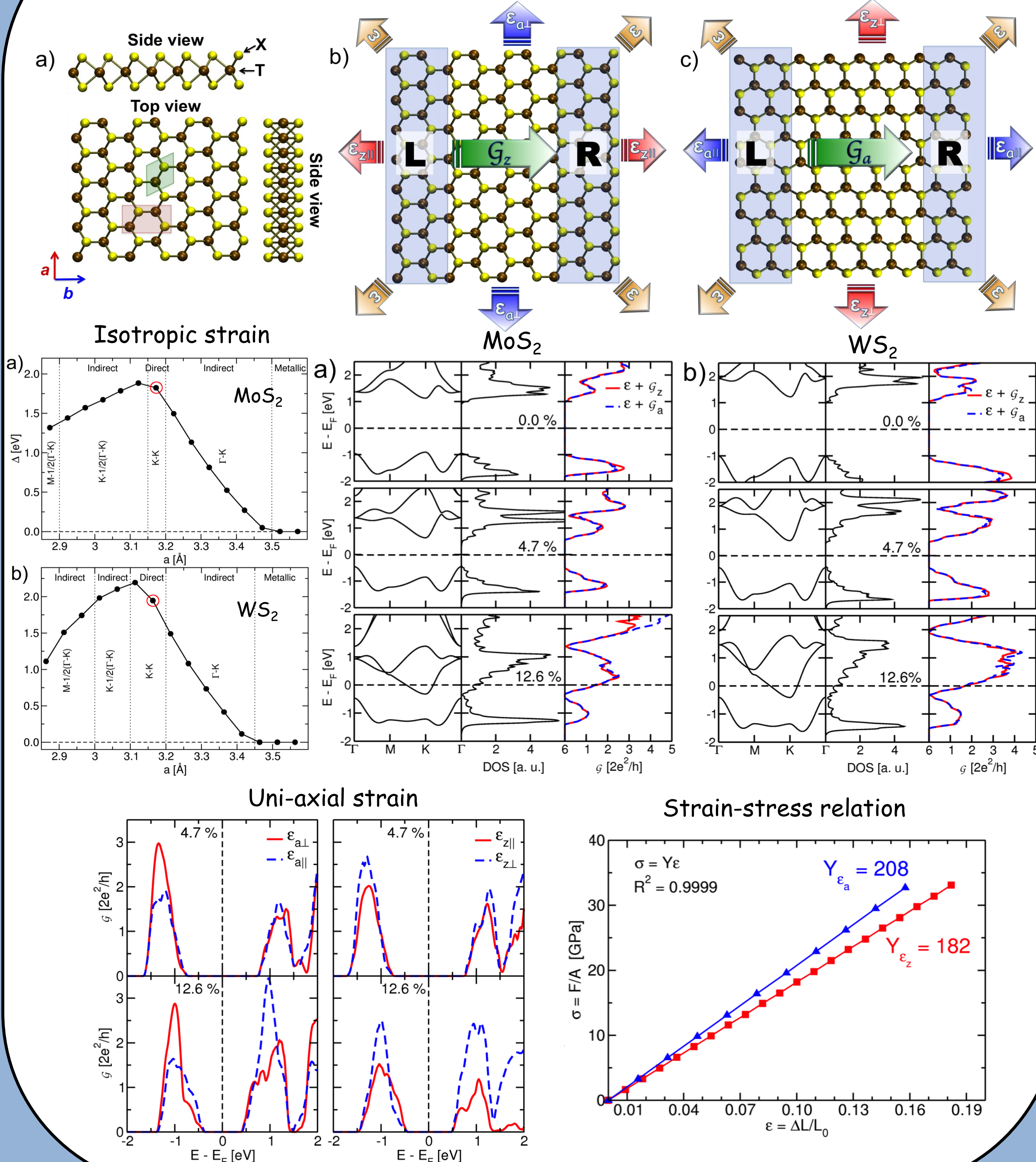
Conductance

$$\mathcal{G}(E) = \frac{2e^2}{h} T(E)$$

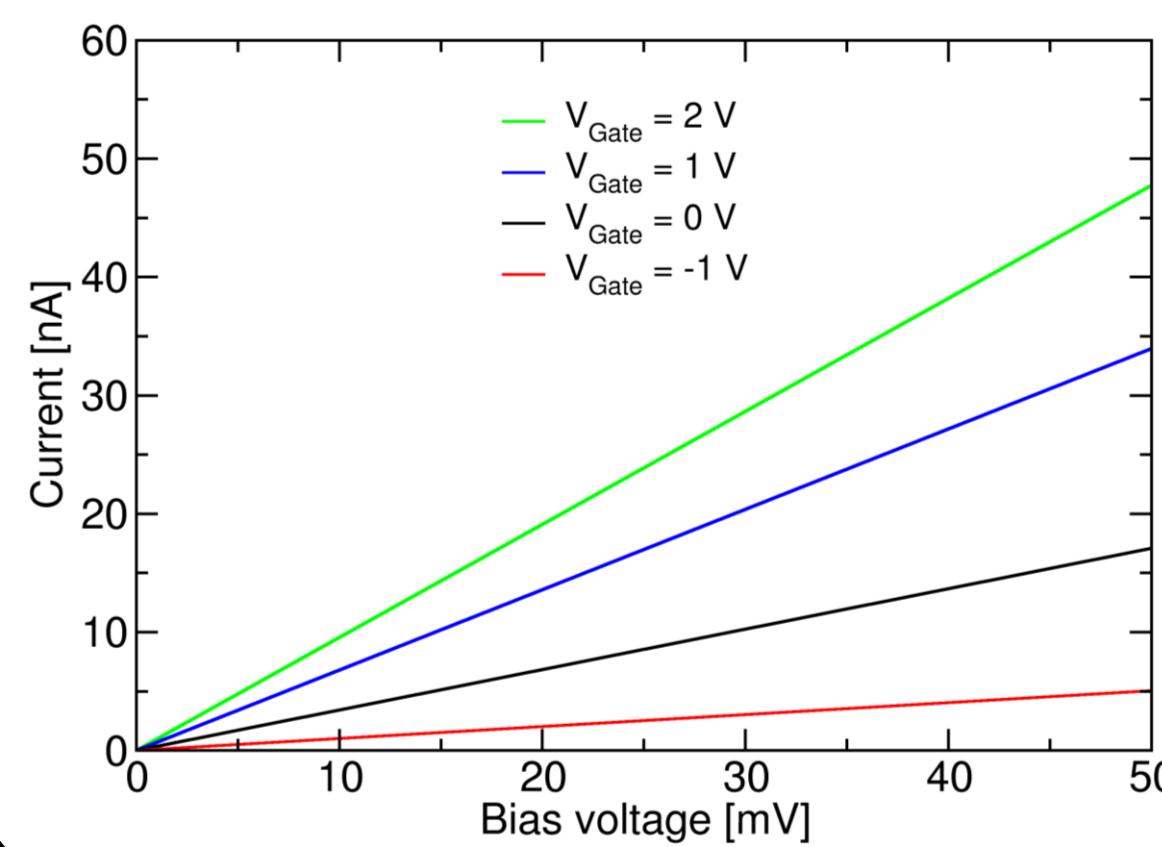
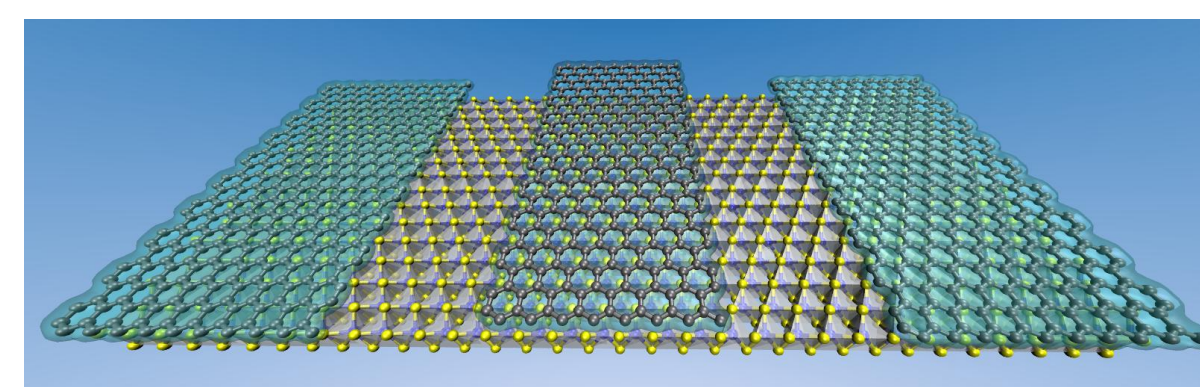
## Local defects



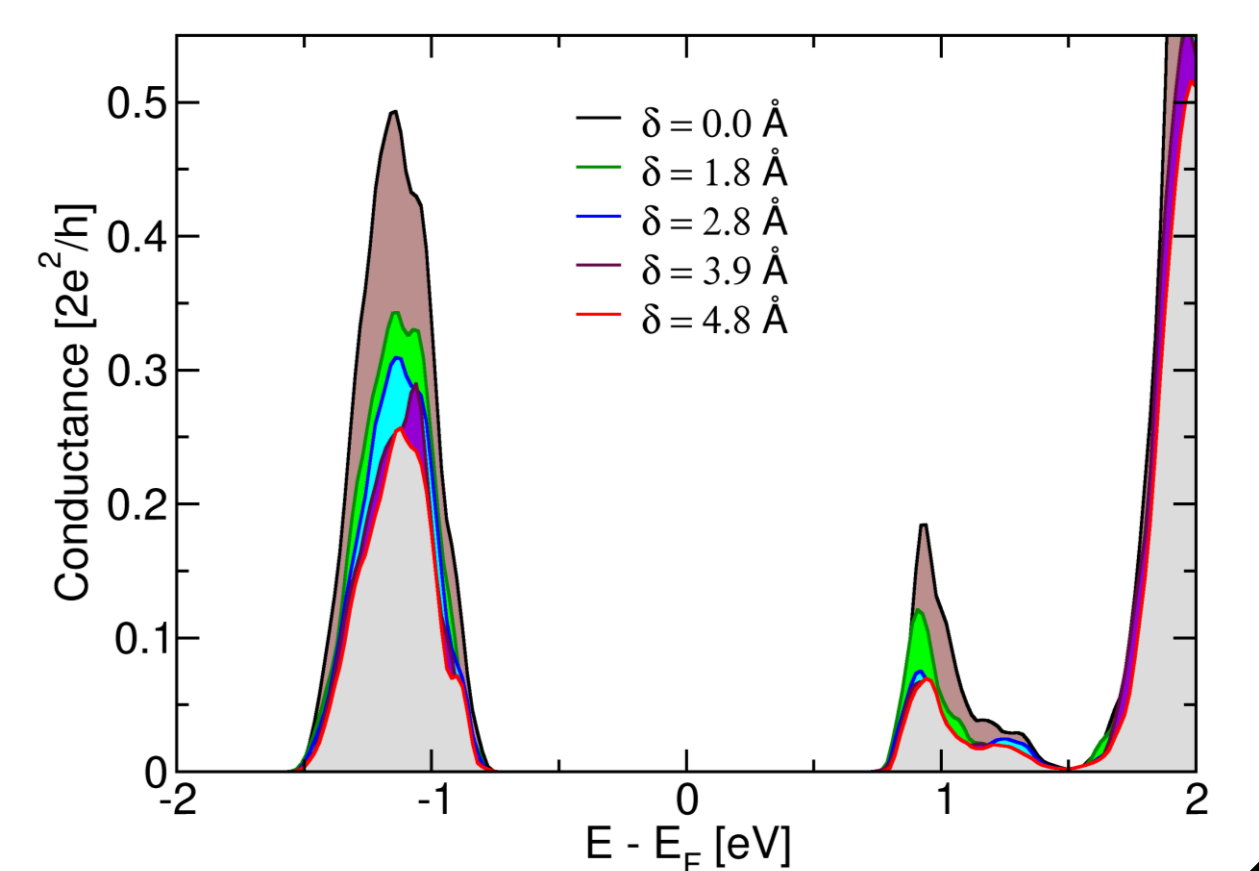
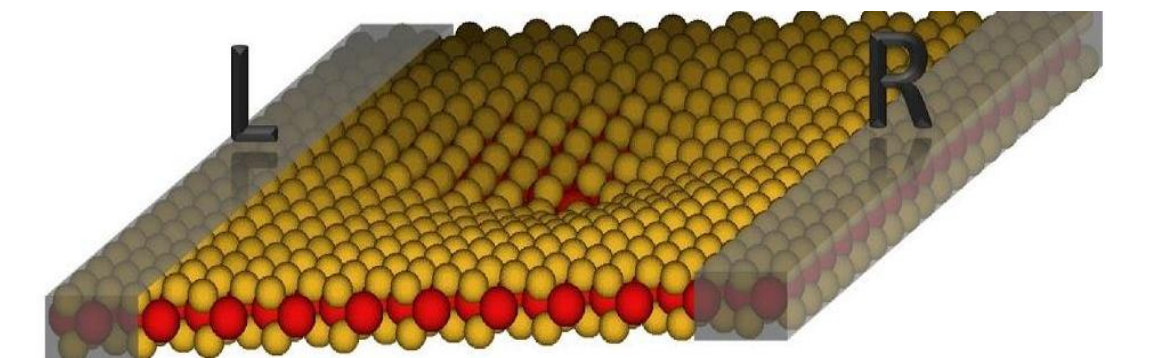
## Isotropic and uni-axial strain



## Graphene and MoS2



## Nano-indentation



## Conclusion

- Local defects cause reduction of conductance in  $\text{MoS}_2$  monolayer, while the band gap changes only slightly.
- The use of graphene as a metallic electrode for  $\text{MoS}_2$  monolayer shows efficient electron injection and ohmic contact through Graphene/ $\text{MoS}_2$ /Graphene junction.
- Tensile strain is a possible way of tuning the band gaps and transport properties of TMD monolayers. The transition semiconductor-metal occurs for elongations as large as 11% for the isotropic strain in  $\text{MoS}_2$  monolayer.
- Local deformation due to the indentation process causes a drop of electron conductance, in our model to 60% of its original value. Thus, the electronic structure of single-layer  $\text{MoS}_2$  is rather robust upon local deformation.

## References

- [1] S. Datta, Quantum Transport: Atom to Transistor, 2nd ed.; Cambridge University Press (2005).
  - [2] Density Functional based Tight Binding, BCCMS, Bremen, Germany. Web: <http://www.dftb-plus.info/>.
  - [3] M. Ghorbani-Asl, R. Juarez-Mosqueda, A. Kuc, T. Heine, *J. Chem. Theory Comput.* 8, 2888 (2012).
  - [4] M. Ghorbani-Asl, S. Borini, A. Kuc and T. Heine, *Phys. Rev. B*, accepted (2013).
  - [5] T. Lorenz, M. Ghorbani-Asl, J. O. Joswig, T. Heine, G. Seifert, *submitted* (2013).
- ✧ This work was supported by FP7-PEOPLE-2009-IAPP QUASINANO and FP7-PEOPLE-2012-ITN MoWSeS.

